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AMENDMENTS TO THE CLAIMS

- 1. (Cancelled).
- 2. (Original) A resist composition comprising at least one basic compound represented by the general formula (3) formulae (2) to (6):

wherein R^2 , R^3 and R^4 are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

 R^5 , R^7 , R^9 and R^{13} are each independently R^7 is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; and

R⁶-and R⁸-are each independently R⁸ is a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups;

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R¹⁰-is an alkyl-group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, earbonyl, ester, ether, sulfide, earbonate, evano and acetal groups;

R¹¹-is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 2 to 10 carbon atoms;

R¹² is each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, earbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups, or two of R¹² may bond together to form a ring; and n is equal to 2, 3, 4 or 5.

- 3. (Currently Amended) A positive-working resist composition comprising:
- (A) the basic compound of claim 2 claim 1;
- (B) an organic solvent;
- (C) a base resin having an acid labile group-protected acidic functional group which is alkali-insoluble or substantially alkali-insoluble, but becomes alkali-soluble when the acid labile group is eliminated; and
 - (D) a photoacid generator.
- 4. (Original) The positive resist composition of claim 3 which further comprises (E) a dissolution inhibitor.

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5. (Currently Amended) A negative-working resist composition comprising:

(A) the basic compound of claim 2 elaim 1;

(B) an organic solvent;

(C') a base resin which is alkali-soluble, but becomes substantially alkali-insoluble when

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crosslinked with a crosslinking agent;

(D) a photoacid generator; and

(F) a crosslinking agent which induces crosslinkage under the action of an acid.

6. (Original) A patterning process comprising the steps of:

(1) applying the positive resist composition of claim 3 onto a substrate;

(2) heat treating the applied resist, then exposing the heat-treated resist through a

photomask to high-energy radiation having a wavelength of at most 300 nm or an electron beam;

and

(3) heat treating the exposed resist, then developing the resist with a liquid developer.

7. (Original) A patterning process comprising the steps of:

(1) applying the negative resist composition of claim 5 onto a substrate;

(2) heat treating the applied resist, then exposing the heat-treated resist through a

photomask to high-energy radiation having a wavelength of at most 300 nm or an electron beam;

and

(3) heat treating the exposed resist, then developing the resist with a liquid developer.

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8. (Cancelled).

9. (Withdrawn) A basic compound represented by the general formula (3):

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wherein R², R³ and R⁴ are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

R⁷ is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; and

R⁸ is a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups.

10-12. (Cancelled).

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13. (Currently Amended) A compound of the formula:

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14. (Withdrawn) A resist composition comprising the compound of claim 13.